Abstract

This invention relates to an article having a substrate with a photocatalyst coating film formed thereon by ae sputtering method, characterized in that the photocatalyst coating film comprises titanium oxide as a main component and at least one kind of metal having a sputtering rate for Ar being 0.9 to 2.7 times that of Ti, preferably at least one kind of metal selected from the group consisting of Fe, V, Mo, Nb, Al and Cr, in an amount of 0.01 to 10 wt % in terms of the sum of such metals. The coating film is formed by a method using a Ti metal sputtering target or a Ti sub-oxide sputtering target containing the metal in an amount of 0.01 to 10 wt % in terms of the sum of such metals, or a method using two kinds of targets for two sputtering cathodes and applying reversing potential so as to have a cathode and an anode alternately.